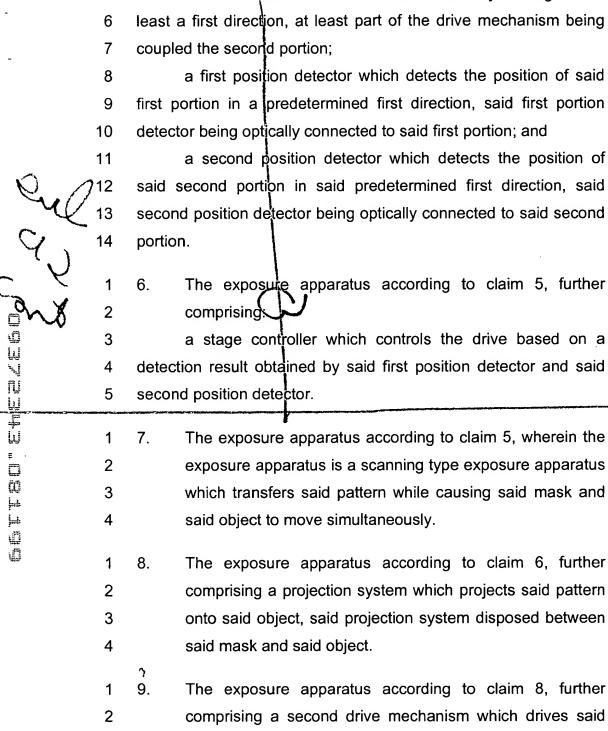
CLAIMS

What is claimed is:

	1	A stage device, comprising:
	2	a movable stage which has a first portion to support an
	3	object and a second portion;
	4	a drive mechanism which drives said movable stage in at
	5	least a first direction, at least part of the drive mechanism being
	6	coupled to said second portion;
	7	a first position detector which detects the position of said
	8	first portion in a predetermined first direction, said first position
	9	detector being optically connected to said first portion; and
	10	a second position detector which detects the position of
	11	said second portion in said predetermined first direction, said
	12	second position detector being optically connected to said second
	13	portion.
g g	1	2. The stage according to claim 1, further comprising:
	2	a stage controller which controls said drive mechanism
ink i	3	based on a detection result obtained by said first position detector
	4	and said second position detector.
	1	3. The stage device according to claim 1, wherein said first
	2	portion and said second portion are integrally formed.
	2	portion and said second portion are integrally formed.
	1	4. The stage device according to claim 1, wherein said drive
	2	mechanism comprises a linear motor.
	1	5. An exposure apparatus which transfers a pattern of a mask
Dul.	2	onto an object, comprising:
	3	an object stage which has a first portion to support said
$\forall \omega$	4	object and a second portion;

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a drive mechanism which drives said object stage in at

object along an axis direction of said projection system.

t in the sector	in a procession	1	10. The exposure apparatus according to claim 1, further
•		2	comprising a second drive mechanism which drives said
		3	object in a direction different from said first direction.
		1	11. An exposure device which exposes a pattern of a mask
		2	onto a substrate, comprising:
		3	a mask stage which positions said mask;
		4	a substrate stage which positions said substrate;
		5	a position detecting device which detects the position of at
	•	6	least one of said mask stage and said substrate stage, said
Qu		7	position detecting device having a moving mirror fixed to at least
حر ۲		8	one of said mask stage and said substrate stage, and a fixed
	J	9	mirror fixed to a reference unit;
	5	10	a correction device which corrects for differences which
*j		11	result from vibration of said fixed mirror; and
		12	a control device which controls the position of said mask
### ##################################		13	and substrate stages in at least one direction based on an output
æ		14	from said correction device.
(3) W 	And to Selver to gain, you are specially the	1	12. The exposure device according to claim 11, further
		2	comprising a projection optical system disposed between said
C C		3	mask and said substrate, said fixed mirror being disposed in said
		4	projection optical system, an image of said pattern being projected
		5	onto said substrate by said projection optical system.
			13. The exposure device according to claim 11, wherein said
		1 2	13. The exposure device according to claim 11, wherein said position detection device detects the position of at least one of
		3	said mask stage and said substrate stage based on light reflected
	1	4	by a fixed mirror arranged in a reference unit, and light which is
So I	Ų –	5	reflected by a moving mirror disposed in at least one of said mask
ور		6	stage and said/substrate stage, said position detection device
- (4	7	including a correction device which corrects for an error which
		,	including a correction device which corrects for all error which

x.	A.	8	originates from vibration of said fixed mirror, and a control device
. A	M	9	which controls said mask and substrate stages based on an
- 20 E	4	10	output from said correction device.
	~ 		14. The exposure device according to claim 13, wherein said
		1	
		2	correction device is a low pass filter.
		1	15. The exposure device according to claim 13, wherein said
6	1	2	correction device is one which corrects for said error based on
de a		3	stage instruction signals which dictate movement of said mask
Ч	S	4	and substrate stages.
		4	AC A most had af manufacturing an expecture device comprising
		1	16. A method of manufacturing an exposure device, comprising
		2	the steps of:
W		3	providing a stage device/having a first stage which movably
ų Ni		4	supports an object;
Ü		5	providing a drive mechanism which drives said first stage in
	1 1	6	at least a first direction, said first stage having a first portion
8		7	coupled to said drive mechanism and a second portion for
g g	US	8	supporting said object, said first stage device configured with a
ļaš i :		9	first position measuring device which measures the position of
Ţ		10	said first portion in a predetermined measurement direction;
		11	providing a first stage control system which controls said
		12	drive mechanism to control the position of said object in said at
		13	least a first direction based on a measurement result obtained by
		14	said first position measuring device; and
		15	assembling said stage device, said drive mechanism, and
		16	said first stage control system to produce a corresponding
		17	exposure device.
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